

EN-204 – Materials for Energy Applications  
Problem Set – Semiconductor Physics

1. A semiconductor device requires n-type material, and it is to be operated at 400K. Would Si doped with  $10^{15}$  atoms/cc of as be useful in this application? Could Ge doped with  $10^{15}$  atoms/cc **as** be used? (make the reasonable assumptions and state them clearly).
2. For silicon doped with  $10^{15}$  #/cc phosphorous atoms find the temperature at which
  - a. The material starts becoming intrinsic (assume that intrinsic condition starts at  $n_i = 10N_d$ )
  - b. The carriers freeze out. (Note: Ideally freeze out occurs at 0K so assume freeze out starts to occur when  $n_0 = 10^{-6}\%$  of  $N_d$ ,  $n_i = 1.5 \times 10^{10}$  /cc).
3. Prior to processing, a certain portion of semiconductor sample contains  $N_D = 10^{14}$  #/cc donors and  $N_T = 10^{11}$  #/cc R-G centers. After processing, the same portion of semiconductor contains  $N_D = 10^{16}$  #/cc and  $N_T = 10^{10}$  #/cc. Did the processing increase or decrease the minority carrier lifetime?
4. The probability that a state is filled at the conduction band edge ( $E_c$ ) is precisely equal to the probability that a state is empty at the valence band edge ( $E_v$ ). Where is the Fermi level located? (do proper derivation)
5. A Si sample is doped with  $10^{14}$  boron atoms/cc and maintained at 470K. Determine the position of  $E_i$  and  $E_f - E_i$ .
6. Derive an expression relating the intrinsic level  $E_i$ , to the center of the band gap  $E_g/2$ . Calculate the displacement of  $E_i$ , from  $E_g/2$  for Si at 300 K, assuming the effective mass values for electrons and holes are  $1.1m_e$  and  $0.56m_e$  respectively.
7. Calculate the electron and hole density in germanium, silicon and gallium arsenide if the Fermi energy is 0.3 eV above the intrinsic energy level. Repeat if the Fermi energy is 0.3 eV below the conduction band edge. Assume that  $T = 300$  K.
8. Taking the semiconductors to be non-degenerate, show that the energy at which the carrier distributions peak is  $E_c + kT/2$  and  $E_v - kT/2$  for the conduction and valence bands, respectively.
9. For a non-degenerate semiconductor, the peak of the electron distribution versus energy inside the conduction band is showed to occur at  $E_c + kT/2$  as per the previous problem. Expressed as a fraction of the electron population at the peak energy, what is the electron population in a non-degenerate semiconductor at  $E = E_c + 5kT$ ?
10. (a) Under equilibrium conditions at  $T > 0$  K, what is the probability of an electron state being occupied if it is located at the Fermi level?

- (b) If  $E_f$  is positioned at  $E_c$  determine the probability of finding electrons in states at  $E_c + kT$ .
- (c) The probability a state is filled at  $E_c + kT$  is equal to the probability that the state is empty at  $E_c + kT$ . Where is the Fermi level located?
11. Calculate the number of states per unit energy in a  $100 \times 100 \times 10$  nm piece of pure perfect silicon 100 meV above and below the conduction band. Write the result in units of  $\text{eV}^{-1}$ .
  12. 4H-SiC is doped with  $2 \times 10^{17} \text{ cm}^{-3}$  nitrogen donor atoms ( $E_c - E_d = 90 \text{ meV}$ ). Use  $N_c = 4 \times 10^{20} \text{ cm}^{-3}$ .
    - a. Calculate the electron density at 300 K.
    - b. Calculate the hole density at 300 K after adding  $2 \times 10^{18} \text{ cm}^{-3}$  aluminum acceptor atoms ( $E_a - E_c = 220 \text{ meV}$ ). Use  $N_v = 1.6 \times 10^{20} \text{ cm}^{-3}$ .
  13. A silicon wafer is doped with Phosphorous atom density of  $3n_i/2$ . Find the number of empty donor states at an energy level 10 meV above the Fermi energy level. Assume that the intrinsic carrier density of the silicon wafer to be  $8.81 \times 10^9 \text{ cm}^{-3}$ . Also calculate the equilibrium electron and hole density of the material @  $T=300 \text{ K}$ . Understand how the carrier concentrations and other parameters would vary, if the dopant induced donor level is present at 100 meV above the Fermi energy level.
  14. To excite the mercury line  $5,461 \text{ \AA}$  an excitation potential of 7.69V is required. If the deepest term in the mercury spectrum lies at  $84,181 \text{ cm}^{-1}$ , calculate the numerical values of the two energy levels involved in the emission of  $5,461 \text{ \AA}$ .
  15. An electron is confined to a 1-micron thin layer of silicon. Assuming that the semiconductor can be adequately described by a one-dimensional quantum well with infinite walls, calculate the lowest possible energy within the material in units of electron volt. If the energy is interpreted as the kinetic energy of the electron, what is the corresponding electron velocity? (The effective mass of electrons in silicon is  $0.26 m_0$ , where  $m_0 = 9.11 \times 10^{-31} \text{ kg}$  is the free electron rest mass).
  16. Find the probability of occupancy of a state of energy (a) 0.05 eV above the Fermi energy (b) 0.05 eV below the Fermi energy (c) equal to the Fermi energy. Assume a temperature of 300 K.
  17. Suppose that the Fermi level in a semiconductor lies more than a few  $kT$  below the bottom of the conduction band and more than a few  $kT$  above the top of the valence band, then show that the product of the number of free electrons and the number of free holes per  $\text{cm}^3$  is given by  $n_e n_h = 2.33 \times 10^{31} T^3 e^{-E_g/kT}$  where  $E_g$  is the gap width.
  18. A current of  $8 \times 10^{-11} \text{ A}$  flows through a silicon  $p-n$  junction at temperature  $27^\circ \text{C}$ . Calculate the current for a forward bias of 0.5V.
  19. Given that a piece of n-type silicon contains  $8 \times 10^{21} \text{ m}^{-3}$  phosphorus impurity atoms, calculate the carrier concentrations at room temperature. It may be assumed that the intrinsic electron concentration in silicon at room temperature is  $1.6 \times 10^{16} \text{ m}^{-3}$ .

20. Find the position of the Fermi level for 11 electrons in an infinite 1D potential well 100Å wide and the probability of exciting a carrier to the first excited state.
21. The  $N_c$  and  $N_v$  of GaAs at 300K are  $4.7 \times 10^{17} \text{ cm}^{-3}$  and  $7 \times 10^{18} \text{ cm}^{-3}$  respectively. Both  $N_c$  and  $N_v$  vary as  $T^{3/2}$ . Calculate the intrinsic carrier concentration at  $T=300\text{K}$  and  $450\text{K}$ . Assume the bandgap is 1.42eV which does not vary with temperature over this range.
22. Band gap of Si depends on the temperature as  
 $E_g = 1.17\text{eV} - 4.73 \times 10^{-4} (T^2/(T+636))$   
 Find a concentration of electrons in the conduction band of intrinsic (undoped) Si at  $T = 77 \text{ K}$  if at  $300 \text{ K}$   $n_i = 1.05 \times 10^{10} \text{ cm}^{-3}$ .
23. Calculate the Fermi function at 6.5 eV if  $E_F = 6.25 \text{ eV}$  and  $T = 300 \text{ K}$ . Repeat at  $T = 950 \text{ K}$  assuming that the Fermi energy does not change. At what temperature does the probability that an energy level at  $E = 5.95 \text{ eV}$  is empty equal 1 %.